

TANTALUM NITRIDE Nanoparticles

Quick Facts

Product	:	Tantalum Nitride Nanoparticles
Stock No	:	NS6130-12-000386
CAS	:	12033-62-4
Form	:	Powder
Purity	:	99.9%
APS	:	80-100nm

Tantalum nitride (TaN) is a chemical compound, a nitride of tantalum. Tantalum nitride is used to create barrier or "glue" layers between copper, or other conductive metals, and dielectric insulator films such as thermal oxides. Tantalum nitride (TaN) films have been shown to provide a barrier to copper diffusion while at the same time promoting good adhesion between the copper lines and the surrounding interlevel dielectric (ILD), the manufacture of integrated circuits, to create thin film surface mount resistors and has other electronic applications. It also has application in thin film resistors. It has the advantage over nichrome resistors of forming a passivating oxide film which is resistant to moisture.



Technical Specification

Molecular Formula	:	TaN
Molecular Weight	:	194.95g/mol
Density	:	14.30g/cm ³
Melting Point	:	2700°C

APS
80-100nm

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NS6130-12-000386

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20ZICE4589C



19ZAZGO1274G



20ZICE4588M

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